

## **ABSTRACT OF THE DISCLOSURE**

The invention relates to photoresist composition suitable for use at 10-165 nm comprising: (a) a polymeric binder (b) a photoactive compound (c) a dissolution inhibitor, the dissolution inhibitor comprising at least (i) two aromatic groups, (ii) fluorine and (iii) a blocked acid group which when unblocked has a  $pK_a < 12$ . Preferred dissolution inhibitors are optionally blocked bisphenol derivatives in which the bridging carbon atom is substituted with a fluorinated aliphatic group.